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For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.



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(54) Title: SLURRY COMPOSITION FOR SECONDARY POLISHING OF SILICON WAFER

(57) Abstract: Disclosed is a slurry composition for secondary polishing of silicon wafers comprising: 2 ~ 10 weight% of colloidal silica having an average particle size of 30 ~ 80 nm; 0.5 ~ 1.5 % by weight of ammonia; 0.2 ~ 1 weight% of a hydroxyalkylcellulose-based polymer for modifying rheology of the composition; 0.03 ~ 0.5 weight% of a polyoxyethylenealkylamine ether-based nonionic surfactant; 0.01 ~ 1 weight% of a quaternary ammonium base and the balance of deionized water.

INTERNATIONAL SEARCH REPORT

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A. CLASSIFICATION OF SUBJECT MATTER

IPC7 H01L 21/304

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

IPC7 B24B 37/00, C09K 3/14, H01L 21/304, H01L 21/306

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched
KOREAN PATENTS AND APPLICATIONS FOR INVENTION SINCE 1975

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)
KIPONET

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	JP 2001-3036 A(FUJIMI INC) 09 JANUARY, 2001 See the whole document	1-6
A	KR 2002-44587 A(SEIMI CHEMICAL CO., LTD) 15 JUNE, 2002 See the whole document	1-6
A	JP 2002-164308 A(NEC CORP; TOKYO MAGNETIC PRINTING CO LTD) 07 JUNE, 2002 See the whole document	1-6
A	KR 10-0289150 B1(CLEAN CREATIVE CO., LTD) 15 FEBRUARY, 2001 See the abstract & claim 1	1-6

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☒ See patent family annex.

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INTERNATIONAL SEARCH REPORT

Information on patent family members

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Patent document cited in search report	Publication date	Patent family member(s)	Publication date
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